

L Number	Hits	Search Text	DB	Time stamp
1	430676	trench recess	USPAT; US-PGPUB	2003/08/22 11:20
2	9412	((trench recess) and fill\$3 near10 (trench recess) near10 (insulat\$3 dielectric oxide)	USPAT; US-PGPUB	2003/08/22 11:20
3	5892	((trench recess) and fill\$3 near10 (trench recess) near10 (insulat\$3 dielectric oxide) and (PR photoresist photo?resist resist))	USPAT; US-PGPUB	2003/08/22 11:20
4	1234	((trench recess) and fill\$3 near10 (trench recess) near10 (insulat\$3 dielectric oxide) and (PR photoresist photo?resist resist)) and spin\$4	USPAT; US-PGPUB	2003/08/22 10:21
5	1562	((trench recess) and fill\$3 near10 (trench recess) near10 (insulat\$3 dielectric oxide) and (PR photoresist photo?resist resist)) and (rotat\$3 spin\$4)	USPAT; US-PGPUB	2003/08/22 11:21
6	337816	trench recess	EPO; JPO; DERWENT; IBM_TDB	2003/08/22 11:20
7	4034	((trench recess) and fill\$3 near10 (trench recess) near10 (insulat\$3 dielectric oxide)	EPO; JPO; DERWENT; IBM_TDB	2003/08/22 11:20
8	431	((trench recess) and fill\$3 near10 (trench recess) near10 (insulat\$3 dielectric oxide) and (PR photoresist photo?resist resist))	EPO; JPO; DERWENT; IBM_TDB	2003/08/22 11:20
9	14	((trench recess) and fill\$3 near10 (trench recess) near10 (insulat\$3 dielectric oxide) and (PR photoresist photo?resist resist)) and (rotat\$3 spin\$4)	EPO; JPO; DERWENT; IBM_TDB	2003/08/22 11:21